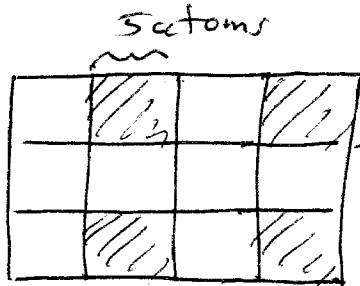


Hmk #2

2.①

1.

Top View



= Ge

= Si

→ similarly in vertical (z) direction

$$L_p = L_{Si} + L_{Ge}$$

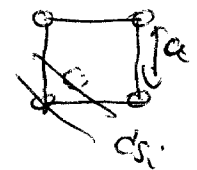
5x atomic spacing
 $= 5d_{Si} + 5d_{Ge}$

$$d_{Si} = \frac{\sqrt{3}}{4} a_{Si}$$

$a =$ cubic lattice constant

$$= 0.3571 \text{ nm Si}$$

$$0.5658 \text{ nm Ge}$$



$$d_{Si} = 0.235 \text{ nm}$$

$$d_{Ge} = \frac{\sqrt{3}}{4} \times 0.5658 \text{ nm} = 0.245 \text{ nm}$$

so $L_{period} = 5 \times 0.235 \text{ nm} + 5 \times 0.245 \text{ nm}$

$$= 2.4 \text{ nm per bit that consists of Ge dot surrounded by Si}$$

a) surface bit density:

$$1 \text{ bit} / (2.4 \text{ nm})^2 = 1.736 \times 10^{13} \text{ cm}^{-2}$$

$$= 17.36 \text{ Terabits/cm}^2 = \rho^{2D}$$

b) volume density

$$1 \text{ bit} / (2.4 \text{ nm})^3 = 7.23 \times 10^{19} \text{ cm}^{-3} = \rho^{3D}$$

c) area for 1 Terabit; $\text{Bits} = \rho^{2D} \times A$

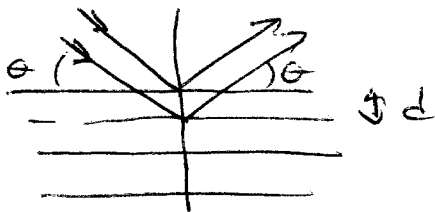
$$A_{IT} = \frac{1 \text{ Tbit}}{17.36 \text{ Tbits/cm}^2} = \frac{1}{17.36} \text{ cm}^2 = 0.0576 \text{ cm}^2$$

d) Bit in $1 \text{ cm}^2 \times 10$ layers.

$$\begin{aligned} \text{Bits} &= 17.36 \text{ Tbits/cm}^2 \times 10 \text{ periods} \\ &= 173.6 \text{ Tbits} \end{aligned}$$

2.]

Bragg diffraction $2d \sin \theta = n\lambda$



$$\theta = \sin^{-1} \frac{n\lambda}{2d}$$

$$\lambda = \frac{2d \sin \theta}{(n = \text{order})} = \frac{2 \times 2.4 \text{ nm} \sin 45^\circ}{1}$$

a) $\lambda = 3.394 \text{ nm}$ for 1st order ($n=1$) at 45°
for every bit active (1111^{bit} pattern)

b) if it were possible to turn every other bit off (1010 --) then $d_{\text{effective}} \rightarrow 2d$

$$\begin{aligned} \theta &= \sin^{-1} \frac{3.394 \text{ nm}}{2 \times 2 \times 2.4 \text{ nm}} = \sin^{-1} [0.3535] \\ &= 20.7^\circ \end{aligned}$$

c) for $\lambda_{\text{CuK}\alpha} = 0.154 \text{ nm} = 1.54 \text{ \AA}$

$$\theta = \sin^{-1} \left[\frac{0.154 \text{ nm}}{2 \times 2.4 \text{ nm}} \right] = \sin^{-1} (0.0321) = 1.84^\circ$$

d) it seems that x-rays could diffract from the quantum dot bit pattern

3) assume that the 20 nm refers to L_G

$$W = 5 L_G = 100 \text{ nm}$$

$$t_{ox} = 0.8 \text{ nm} = 8 \text{ \AA}$$

$$a) \quad f_T = \frac{v_{sat}}{2\pi L_G} \rightarrow v_{sat} = 2\pi L_G f_T$$

$$= 1.5 \text{ THz}$$

$$v_{sat} = 2\pi \times 20 \text{ nm} \times 1.5 \text{ THz}$$

$$= 1.885 \times 10^7 \text{ cm/sec}$$

b) This is realistic because v_{sat} for Si
 $v_{sat} \sim 1 \text{ to } 2 \times 10^7 \text{ cm/sec}$

c) how many e^- on gate with $V_{GS} - V_T = 1 \text{ volt}$.

$$C_{ox} = \frac{\kappa_{ox} \epsilon}{t_{ox}} = \frac{3.9 \times 8.85 \times 10^{-14} \text{ F/cm}}{0.8 \times 10^{-7} \text{ cm}}$$

$$= 4.3 \times 10^{-6} \text{ F/cm}^2 = \frac{4.3 \times 10^{-6} \text{ F}}{10^8 \mu\text{m}^2 = 1 \text{ cm}^2}$$

$$= 43 \text{ fF}/\mu\text{m}^2$$

$$d) \quad C = \frac{\Delta Q}{\Delta V} \quad Q = qN = C\Delta V$$

$$N = \frac{43 \text{ fF}/\mu\text{m}^2 \times 1 \text{ V} \times (20 \text{ nm} \times 100 \text{ nm})}{q = 1.6 \times 10^{-19} \text{ C}}$$

$$N_{\text{gate}} = 539 \text{ electrons}$$